

# Week 2-10

Optical Detectors 5

OPV Modules

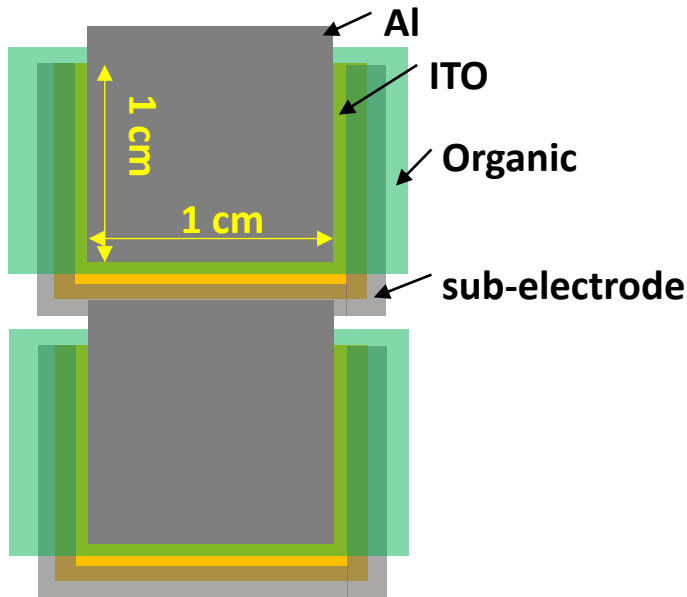
Ch. 7.9 – 7.10



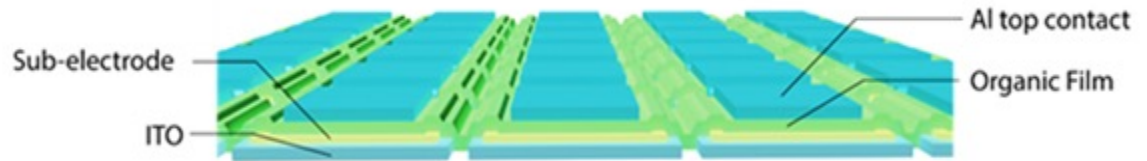
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# Scaling to Modules

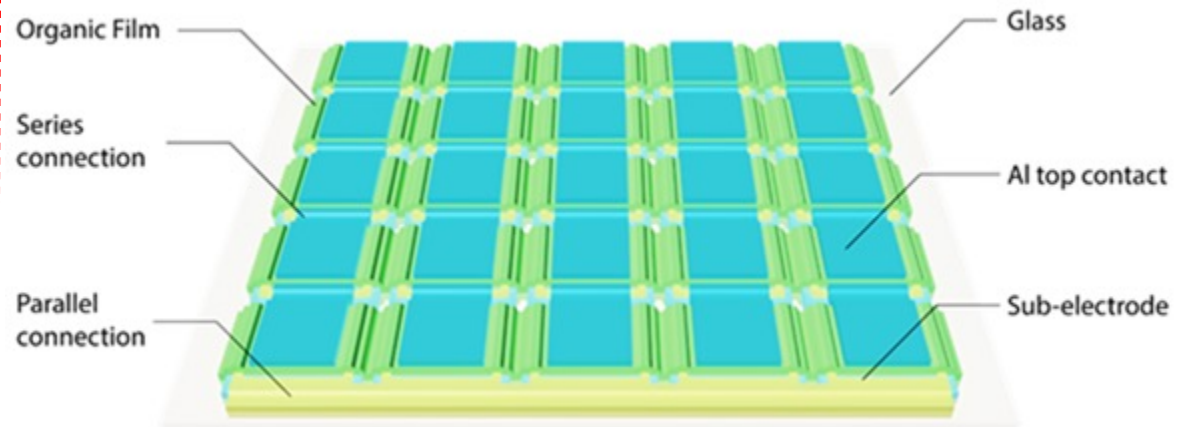
## Two tandem cells in series



## Front view



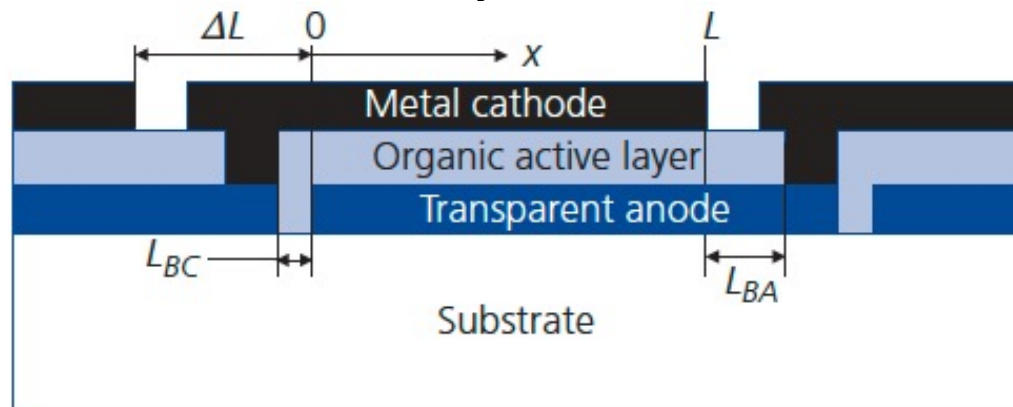
## Top view



- Surrounding cell with contacts (sub electrodes) reduces resistance
- 5x5 discrete tandem cells connected in series-parallel configuration
- Active area: 1 cm<sup>2</sup> for discrete; 25 cm<sup>2</sup> for module

# Power Limiting Resistances in the Module

- **Geometric fill factor** accounts for inactive regions from device interconnects:  $\eta_{p,module} = GFF \cdot \eta_{p,cell}$



Material	Layer thickness	$R_{\square}$ ( $\Omega/\text{sq.}$ )
Al	135	0.16
ITO on glass	150	12.5
ITO on PET	150	50
PEDOT:PSS PH1000	150	100

Material	$\rho_C$ with Al ( $\text{m}\Omega \text{ cm}^{-2}$ )
ITO on glass	11
ITO on PET	17
PEDOT:PSS PH1000	200

## Components Leading to Module Efficiency Loss

$$\Delta P_{sheet} = \frac{R_{\square}}{W} \int_0^L I(V)^2 dx = \frac{R_{\square}}{W} \int_0^L [j(V)Wx]^2 dx = I(V)^2 \left[ \frac{R_{\square} L}{3W} \right]$$

Power loss from contact sheet resistance,  $R_{\square}$

$$R_{sheet} = \frac{R_{\square} L}{3W}$$

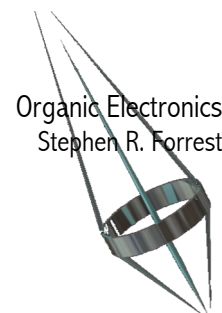
Total sheet resistance from contact of length, L, device width W

$$R_{BA,C} = R_{\square,A,C} \frac{\Delta L}{3W}$$

Bridge resistance

$$R_C = \rho_C \frac{3}{W \Delta L}$$

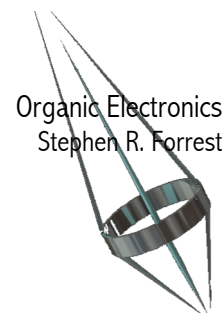
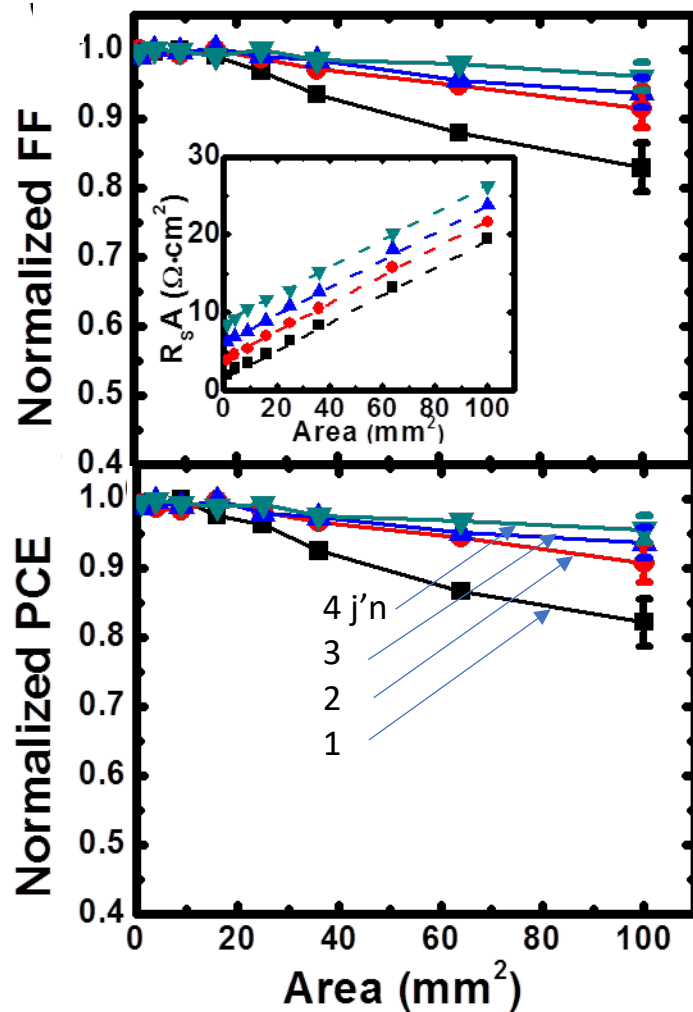
Contact resistance between cathode and anode



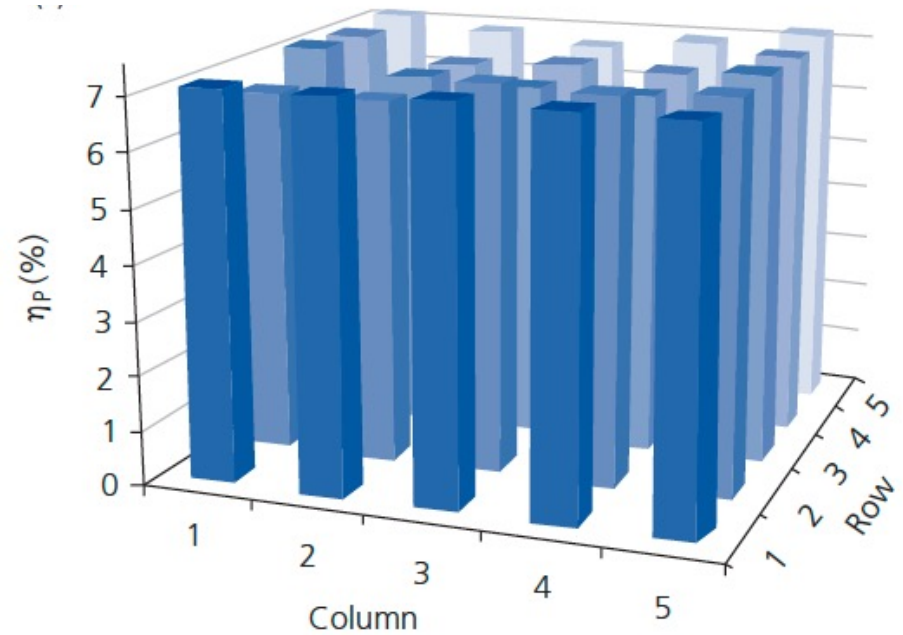
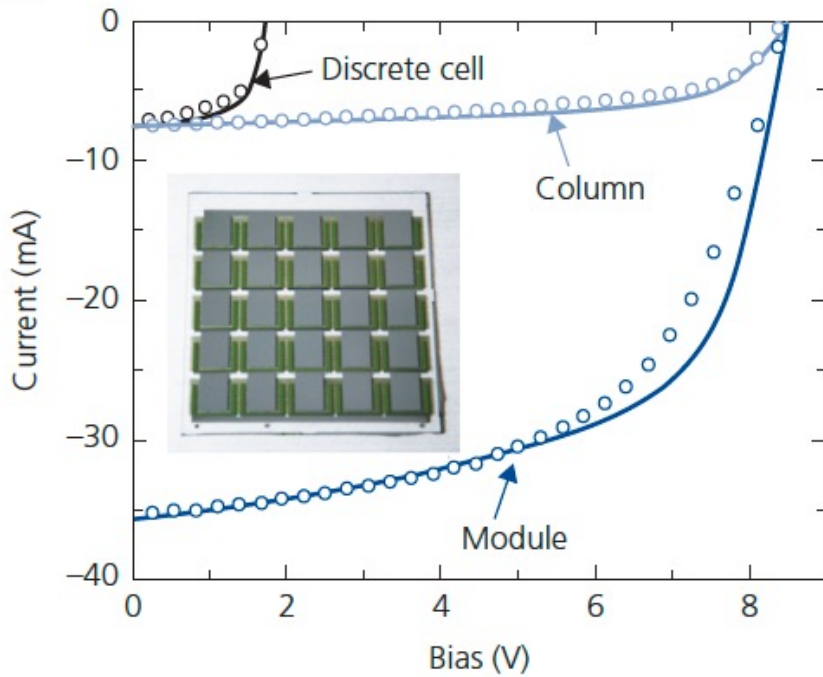
# Multijunction Cells Limit the Effects of Resistance

The higher the voltage,  
The smaller the problem

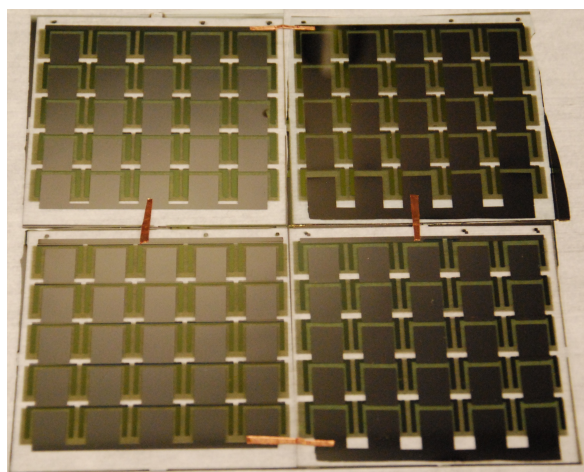
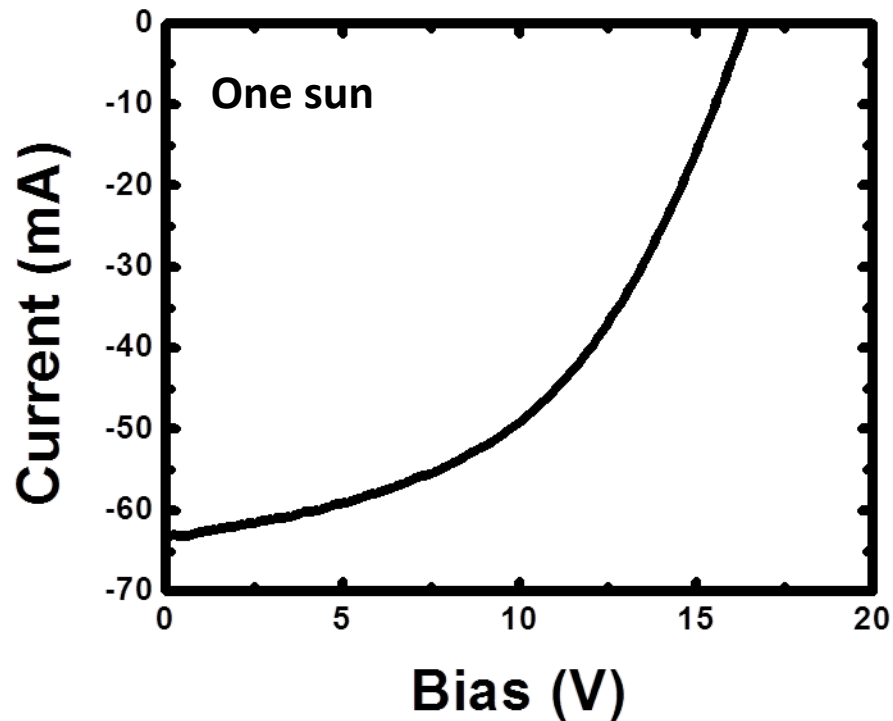
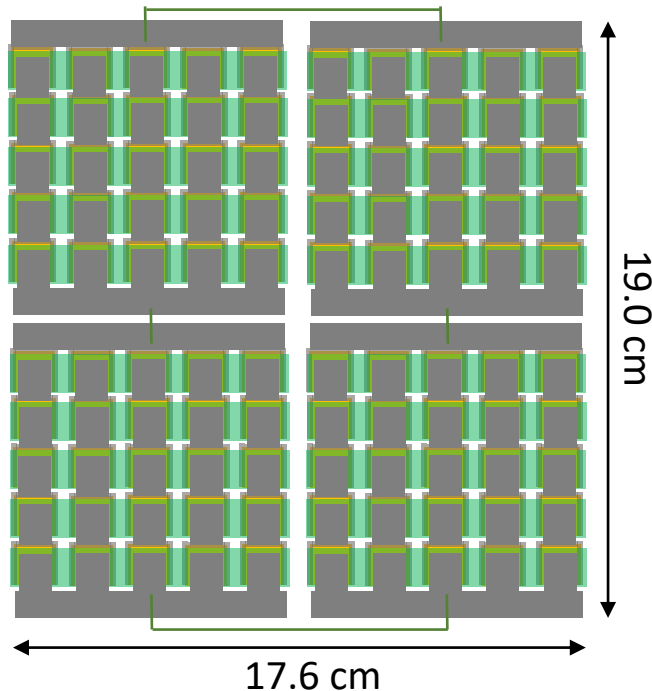
⇒ Multijunction cells



# Efficiency of Tandem Modules in Series-Parallel Circuit



# Tethered 10 x 10 OPV Module



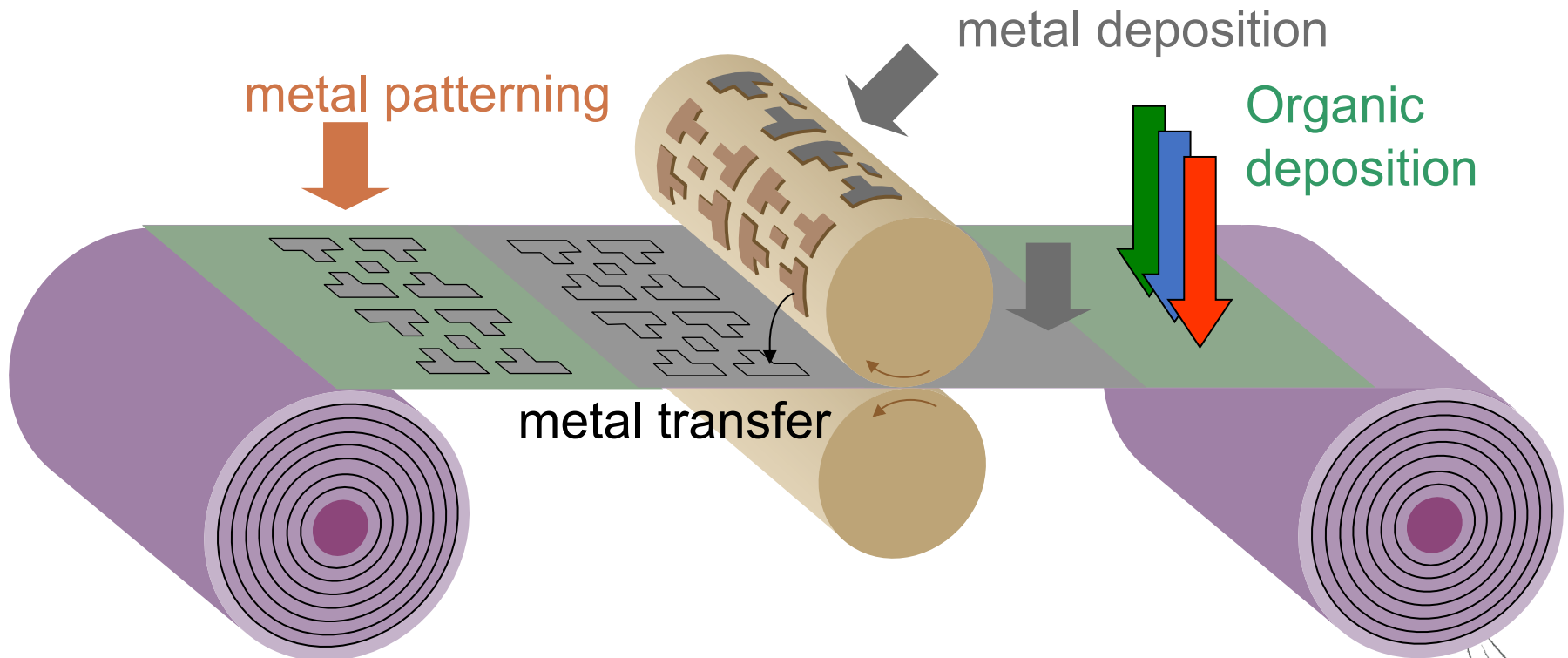
## Module

$I_{SC} = 63 \text{ mA}$ ,  $V_{OC} = 16.4 \text{ V}$ ,  $FF = 50\%$ ,

Output power = 519 mW, PCE = 5.2%

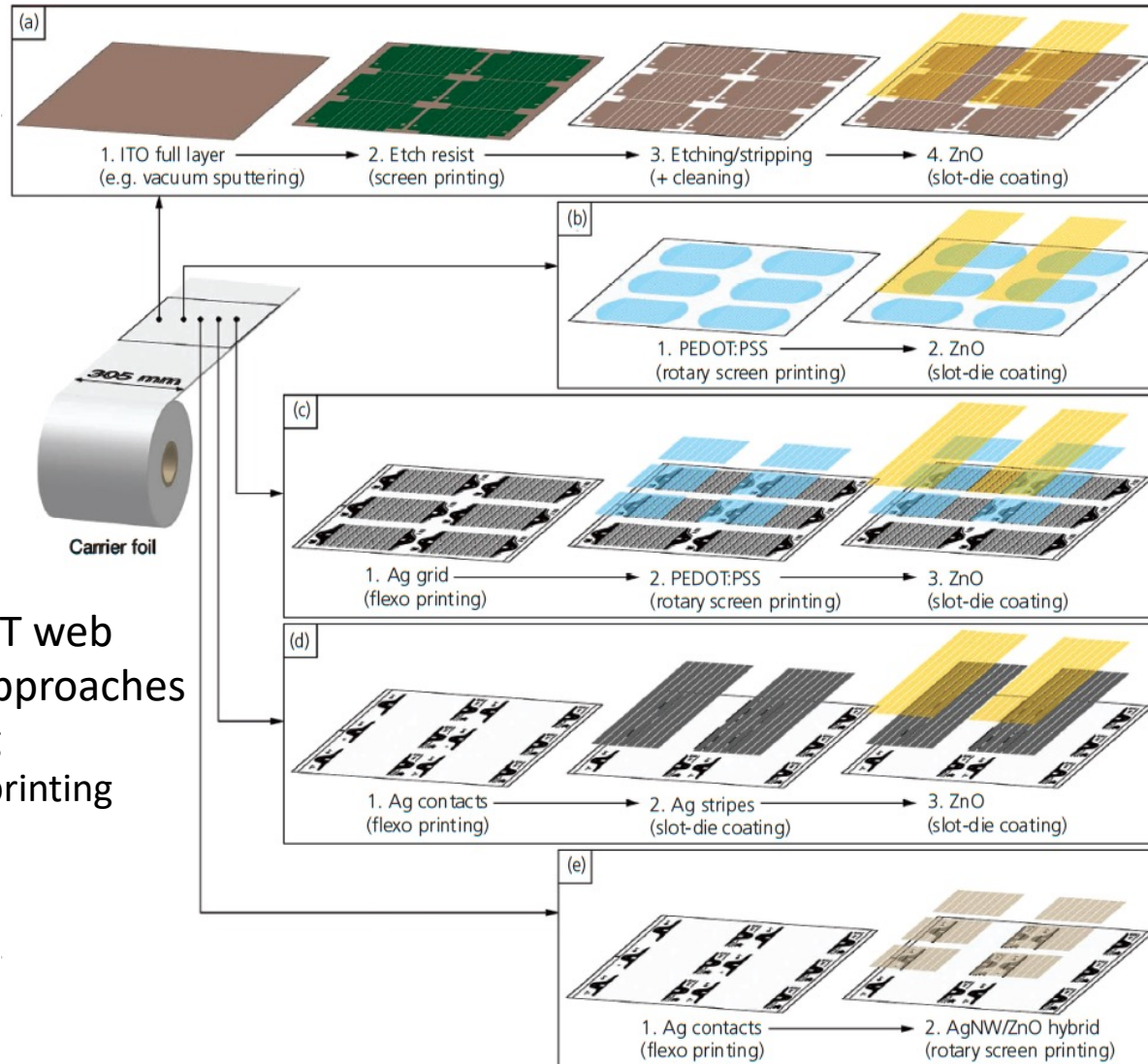
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# Manufacturing of Solar Cells by R2R Methods





# Printing Methods Used in R2R Solar Cell Production



305 mm wide PET web  
Many possible approaches

- Slot-die coating
- Rotary screen printing
- Flexo printing
- Laser scribing  
(see Ch. 5)



# What we learned

- Photoconductors, photodiodes, solar cells are three species of optical detectors
  - Detectors are fundamentally limited by a gain-bandwidth product
  - Solar cells are photodiodes operated in the 4<sup>th</sup> j-V quadrant
- Photodiodes are designed for detection in narrow spectral ranges
  - OPDs have shown high bandwidth, color agility and low noise
- Solar cells have been intensively investigated due to their
  - High efficiency (now ~18% for single junction cells)
  - Transparency in the visible but >10% efficiency via absorption in the NIR
  - Efficiency is intimately linked to the morphology and chemistry of the D-A materials forming bulk HJ
  - Efficiency of OPVs paced by advances in acceptor molecules
- OPVs have demonstrated intrinsic lifetimes of thousands of years
- OPVs thermodynamically limited to <25% due to losses in forming CT states
  - The limit can be exceeded using multijunction cells, singlet fission
- Both solution and vapor deposited OPVs have been “manufactured” using high volume R2R deposition processes



# Organic Thin Film Transistors

## Thin Film Transistors 1

OTFT Basics  
Operating Principles

Ch. 8.1 – 8.3.3



# OTFT Objectives

- Learn how they work
- Learn how they are made
- Learn about their operational reliability
- Learn what they are good for: Are they an answer waiting for a question?
  - Sensing
  - Medical applications

# Advantages vs. Limitations of OTFTs

- PROs

- Flexible, conformable, ultralight
- Can be made over very large areas
- Suitable for large scale R2R manufacture

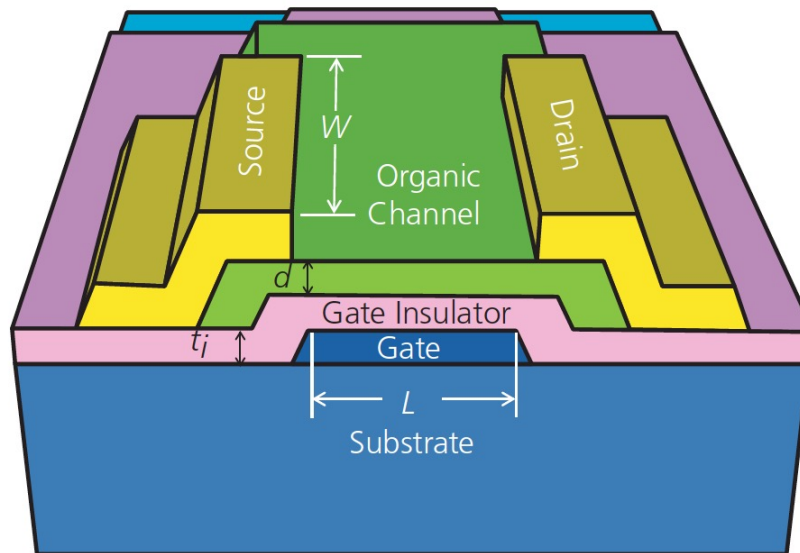
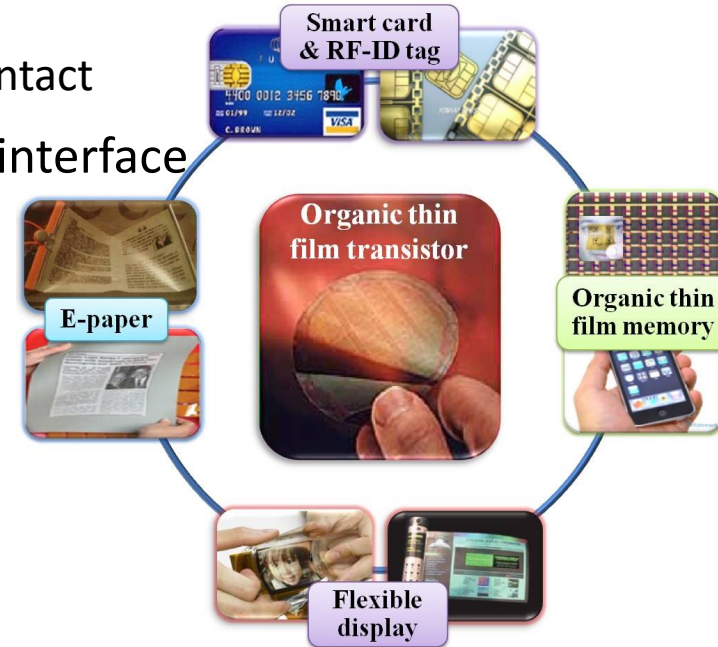
- CONs

- Cannot source large currents
- Characteristics drift over long periods in operation
- Limited bandwidth ( $\leq 1$  MHz in many cases)



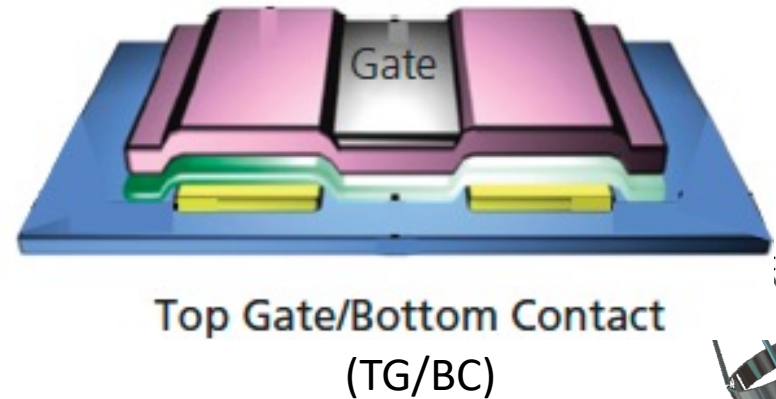
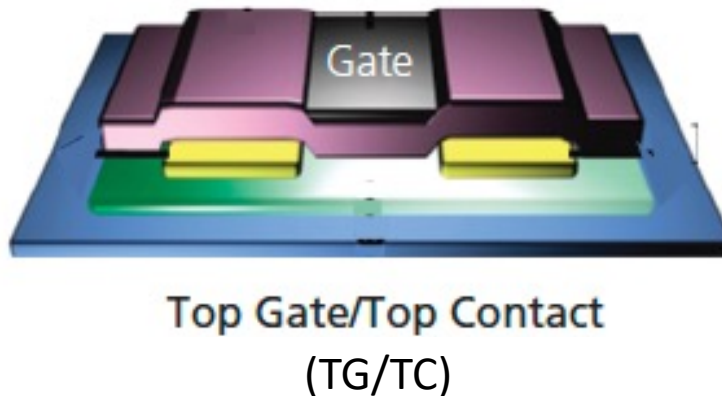
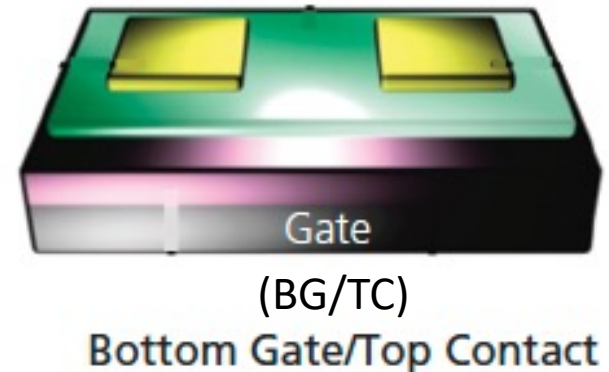
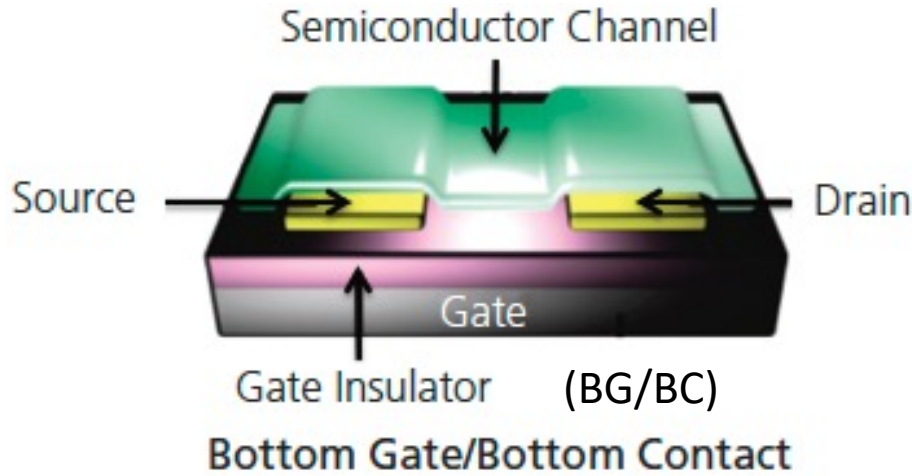
# What an OTFT looks like

- Several different configurations
  - Bottom gate, top gate, bottom SD contact, top SD contact
- Properties strongly influenced by dielectric/organic interface
- Configuration similar to inorganic TFTs
  - Metal oxide
  - a-Si
  - Etc.



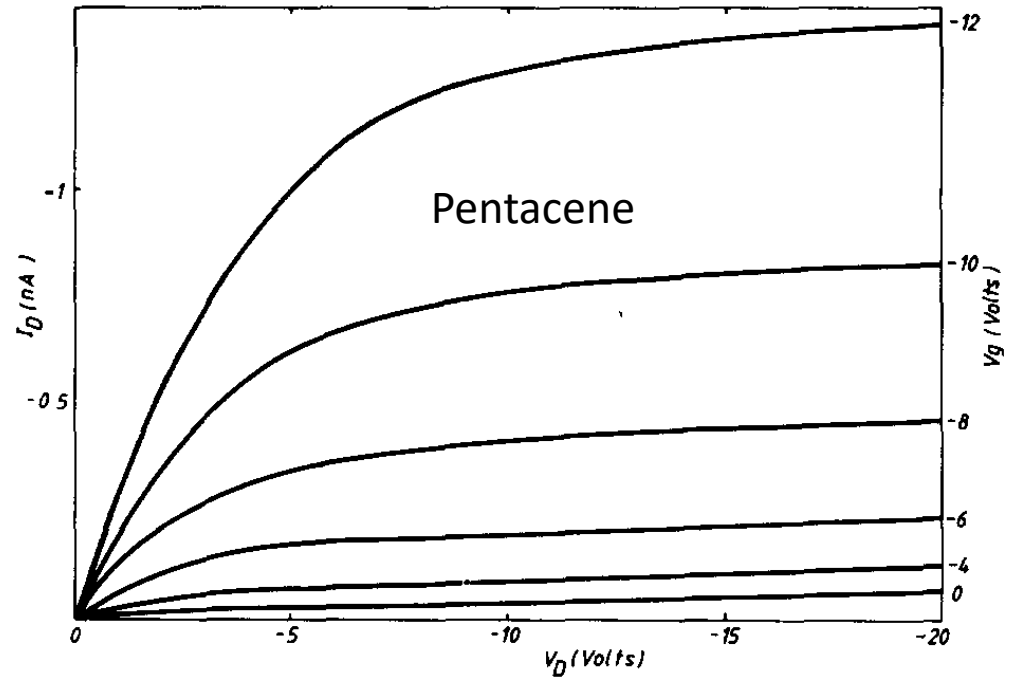
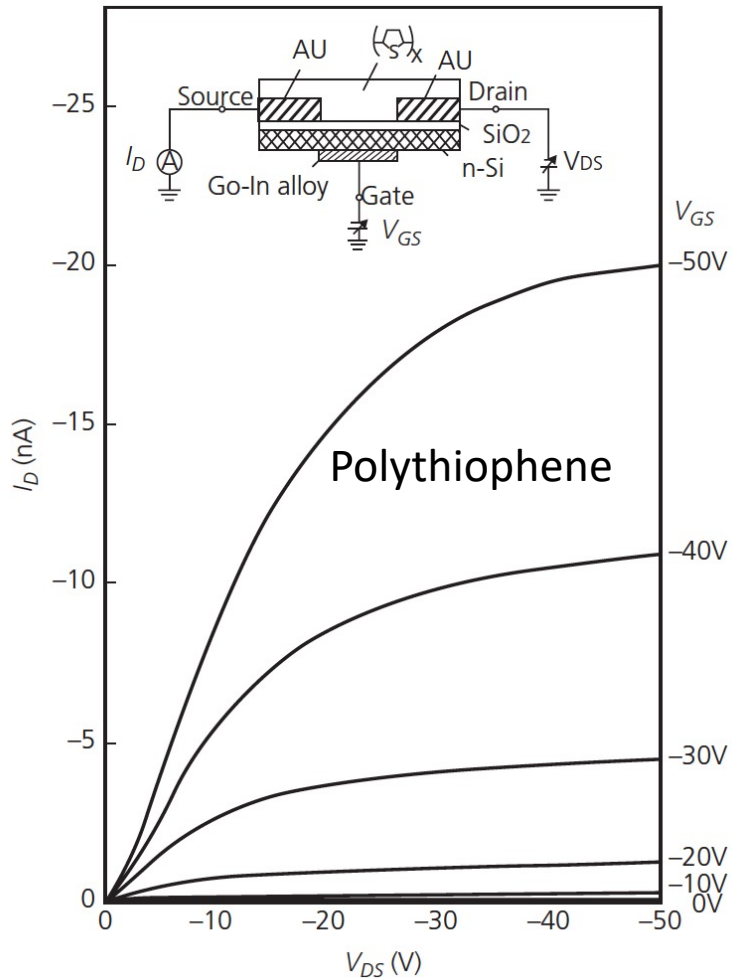
Definitions of Contacts and Dimensions

# Different Contact Arrangements



# Organic Thin Film Transistors

## First demonstrations



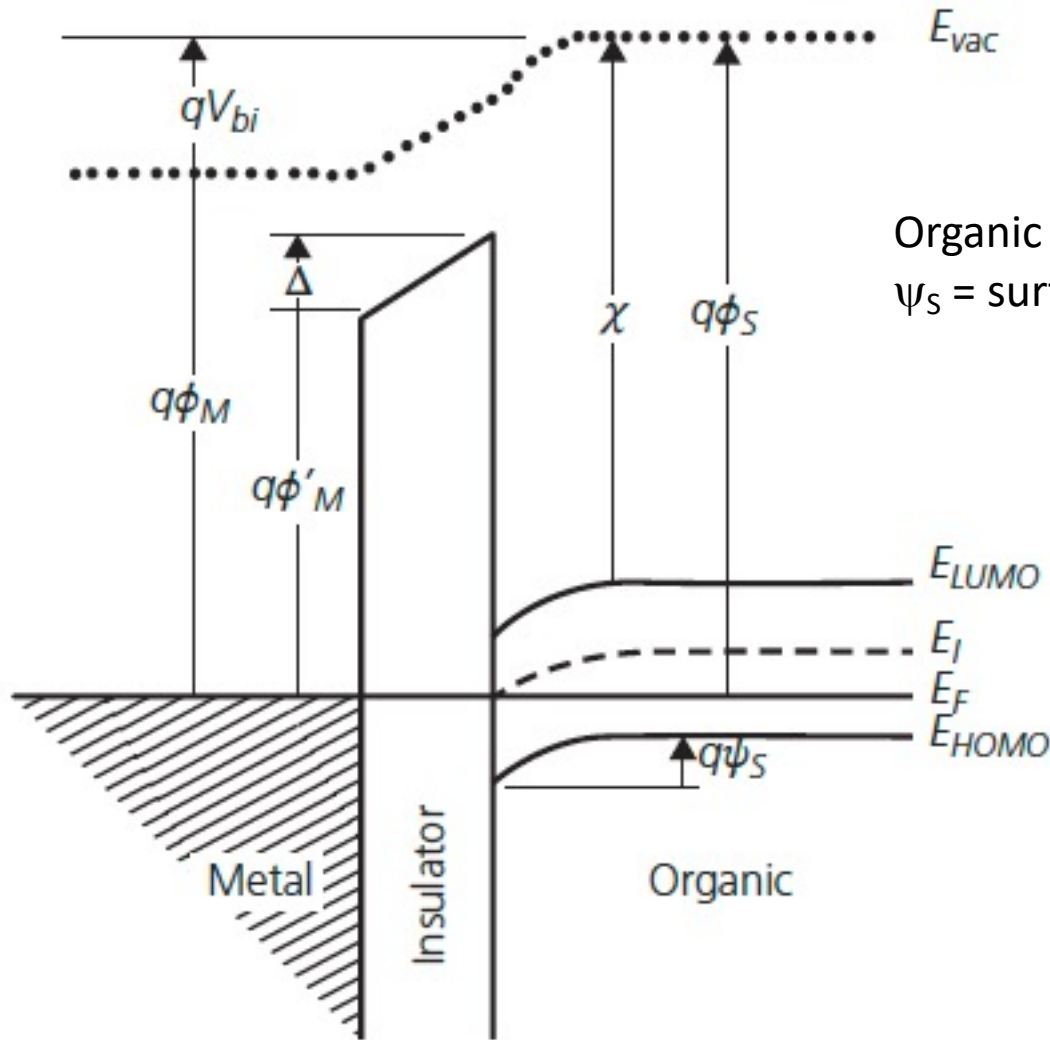
A. Tsumura, et al., Appl. Phys. Lett., (1986) 1210,49

G. Horowitz, et al., Solid State Commun., 72 381 (1989)

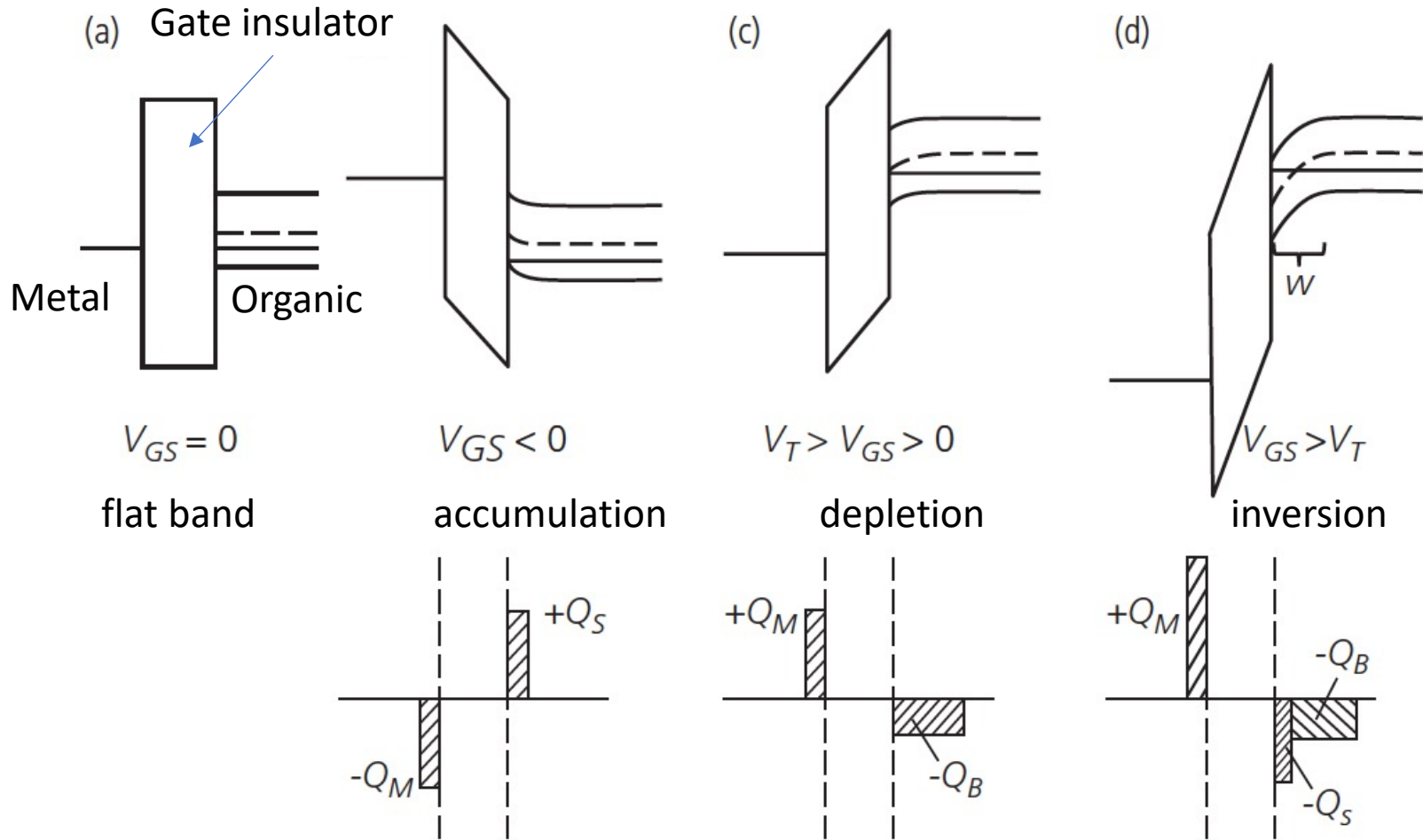
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# Equilibrium Energy Level Diagram at the Gate of the OTFT

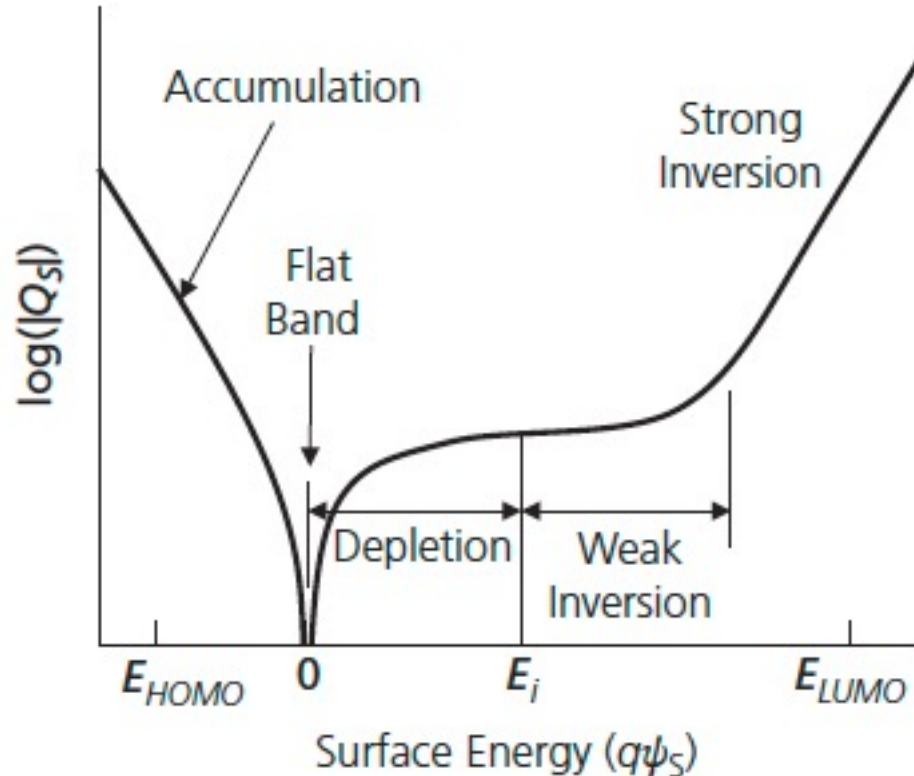


# The MIS Capacitor: Building Block of the OTFT



- Organics often have little charge in the bulk of the semiconductor  $\Rightarrow$  no band bending
- Charge drawn into channel from source to allow conduction at the insulator/org. interface

# Operating Regions of the Transistor



- Since charge is injected from the source, and the channel organic is rarely doped, the OTFT operates in the **accumulation regime**
- The **inversion regime** is rarely relevant in OTFTs for these reasons
- The transistor channel is normally depleted at  $V_{GS} = 0$ , and hence the transistors are **enhancement mode** devices

# How an OTFT Works: Accumulation

Charge injected from the source by a gate voltage,  $V_{GS}$ , at very low drain voltage,  $V_D$ , and hence low channel current (i.e. ohmic):

$$Q(x) = n(x)qt = C_G (V_G - V(x))$$

↖ Charge layer thickness

But contact resistance and potential, charge trapping, grain boundaries, etc. prevent channel conduction until a threshold voltage  $V_T$  is reached:

$$Q(x) = n(x)qt = C_G (V_G - V_T - V(x))$$

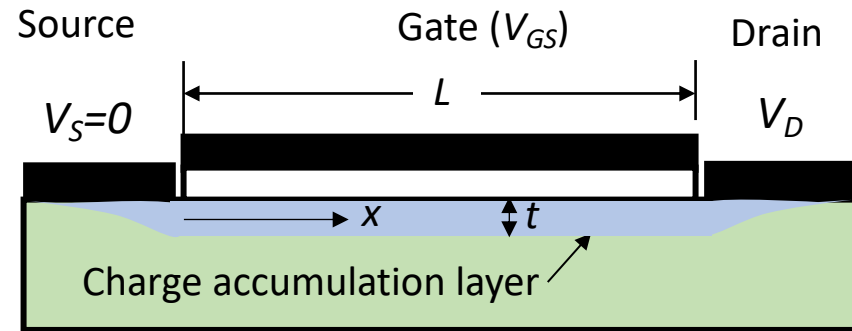
Following Ohm's Law:

$$I_D = A\sigma F = W \overbrace{(n_{ave}qt)}^{Q_{ave}} \mu \frac{V_D}{L}$$

At low voltage, conduction is ohmic  $\Rightarrow$  we can use the average channel voltage drop  $V_D/2$ .

Or, in the linear regime of operation:

$$I_D = \frac{W}{L} C_G \mu \left( V_G - V_T - \frac{V_D}{2} \right) V_D = \frac{W}{L} C_G \mu \left( (V_G - V_T) V_D - \frac{V_D^2}{2} \right)$$



Field-effect mobility is **not** bulk mobility

$$\mu = \mu_{FE}$$

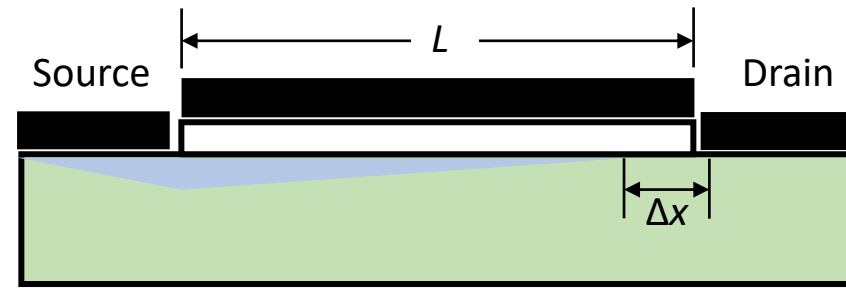
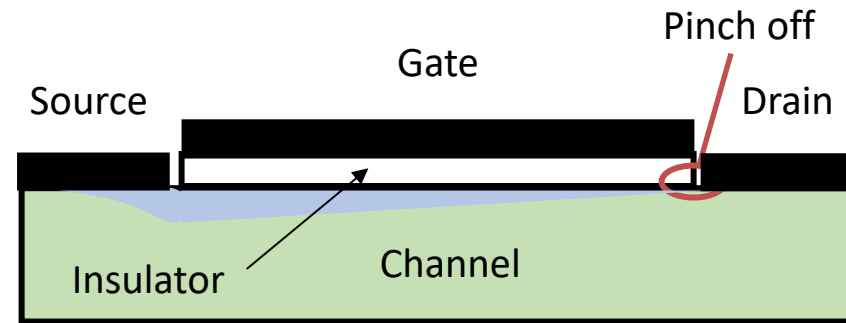
# In the Saturation Region

In the linear regime ( $V_G - V_T \gg V_D$ ), we calculate the transconductance:

$$g_m = \left. \frac{\partial I_D}{\partial V_G} \right|_{V_D} = \frac{W}{L} C_G \mu_{lin} V_D$$

And the output conductance:

$$g_o = \left. \frac{\partial I_D}{\partial V_D} \right|_{V_G} = \frac{W}{L} C_G \mu_{lin} (V_G - V_T)$$



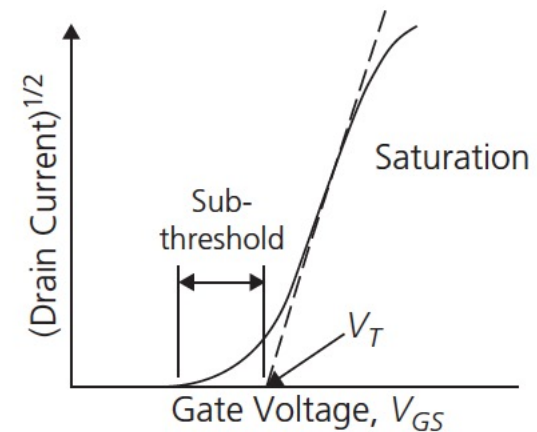
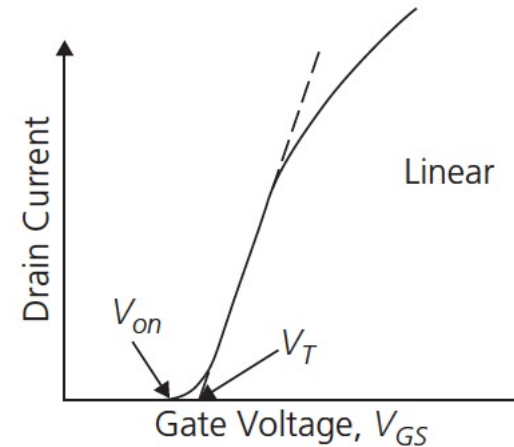
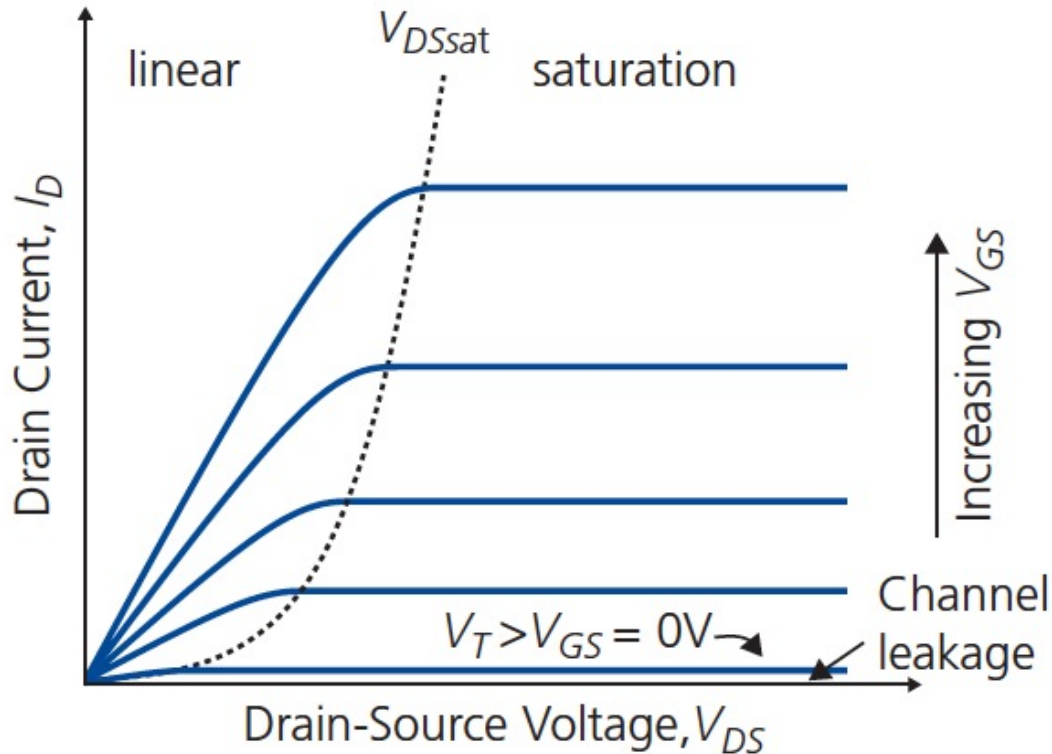
Due to contact and other parasitic resistances,  $\mu_{lin}$  gives errors, so mostly use saturation characteristics:

- When  $V_D = V_G - V_T$ , the channel **pinches off**
- Between pinchoff point and drain,  $n \rightarrow 0 \Rightarrow F \rightarrow$  large to maintain current continuity ( $j = nq\mu F$ )
- No more current (except leakage) enters channel with increasing  $V_D$ , hence we are in the saturation regime.

Then: 
$$I_D = \frac{W}{2L} C_G \mu_{sat} (V_G - V_T)^2$$

Plot of  $I_D^{1/2}$  vs.  $V_G$  gives both  $\mu_{sat}$  and  $V_T$

# Ideal Unipolar OTFT Characteristics



$$I_D = \mu \frac{W}{L} C_G ((V_G - V_T)V_D - \frac{V_D^2}{2})$$

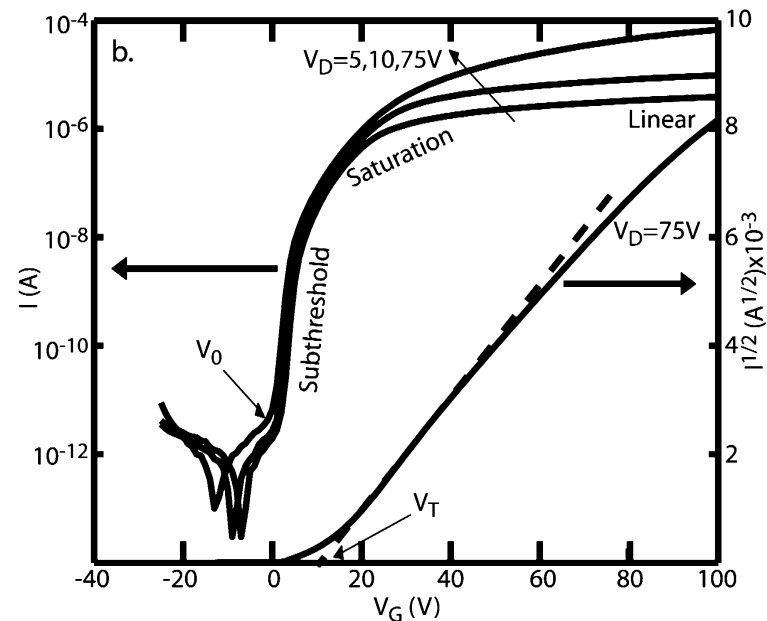
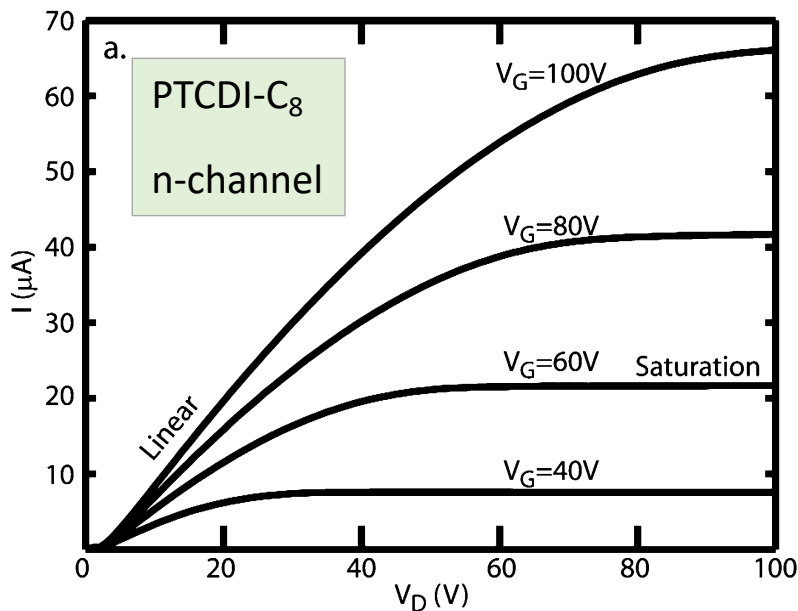
$$g_m = \left. \frac{\partial I_D}{\partial V_G} \right|_{V_D} = \frac{W}{L} C_G \mu_{lin} V_D$$

$$I_D = \frac{W}{2L} C_G \mu_{sat} (V_G - V_T)^2$$

$$g_o = \left. \frac{\partial I_D}{\partial V_D} \right|_{V_G} = \frac{W}{L} C_G \mu_{lin} (V_G - V_T)$$

# DC Characteristics of an OTFT

- Pentacene most frequently employed small molecule for OTFT
- $\mu_{FE} \sim 1 - 1.5 \text{ cm}^2/\text{V-s}$
- DC mobility as high as  $40 \text{ cm}^2/\text{V-s}$  measured in rubrene using OTFTs: is it reliable? (Takeya, et al. Appl. Phys. Lett. **90** 102120 (2007))
- OTFTs measure interface conductance, not mobility.

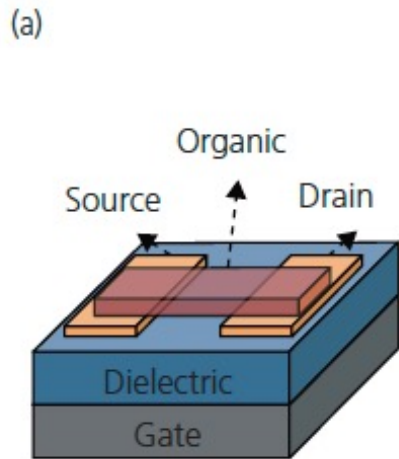




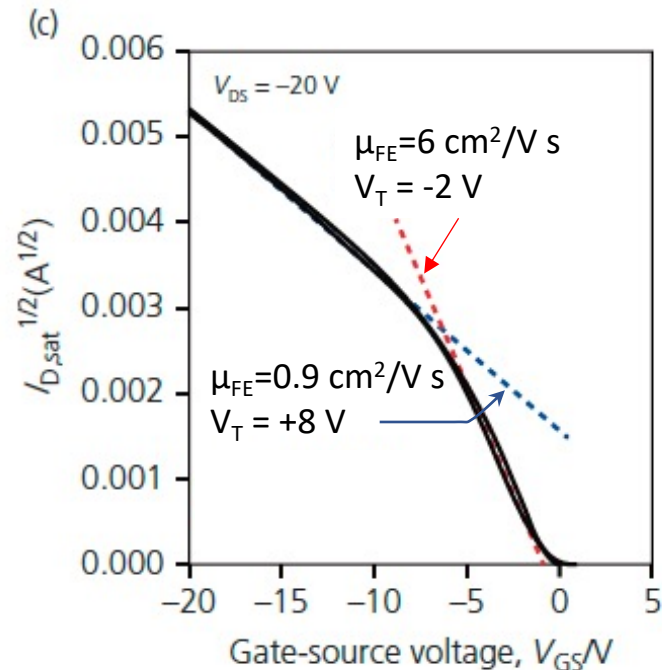
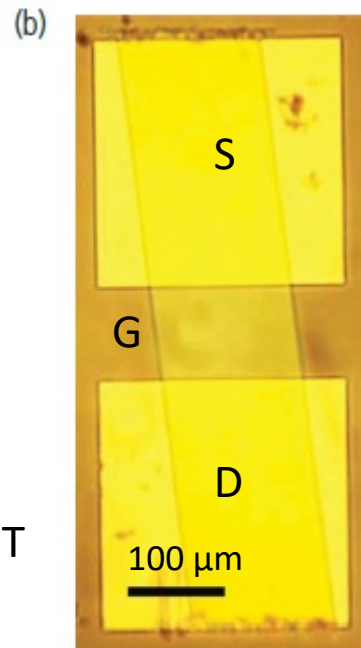
# Equating Field Effect With Bulk Mobilities

- What could go wrong?

Two  $\mu_{FE}$  and  $V_T$  extracted from  $I_D$ - $V_{GS}$  characteristics: Which is right?  
⇒ OTFT does not follow conventional theory due to exponential distribution of states near conduction level edge



rubrene single crystal OTFT

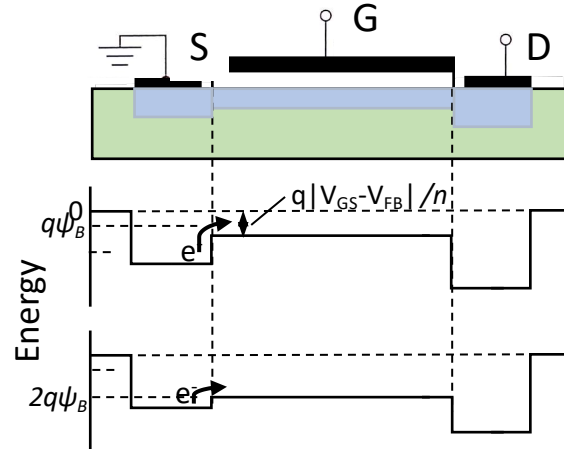


# Subthreshold slope

- Measure of how small a voltage swing needed to turn on a transistor
- Determines noise margin of a circuit (i.e. how easy is it for a “1” to be mistaken for a “0”)

Definition: 
$$S = \frac{\partial V_{GS}}{\partial(\log_{10} I_D)}$$

@  $V_{on} < V_{GS} < V_T$



Leakage due to thermionic emission from contact regions

Imperfect contacts, traps lead to injection barrier at source:

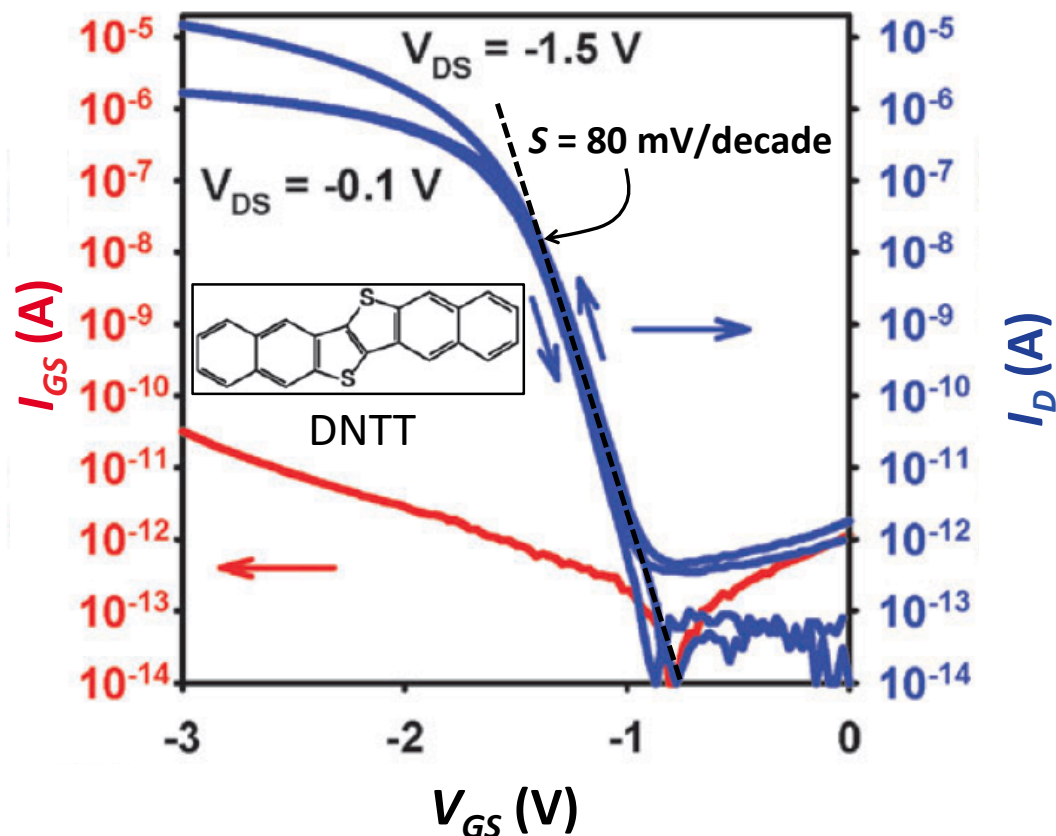
$$I_D = I_{D0} \exp\left(\frac{q|V_{GS} - V_{FB}|}{nk_B T}\right) = I'_{D0} \exp\left(\frac{qV_{GS}}{nk_B T}\right)$$

$$\Rightarrow S = 2.3 \frac{nk_B T}{q} \quad n = 1 \Rightarrow S = 60 \text{ mV/decade}$$

Theoretical minimum slope

# A high performance OTFT

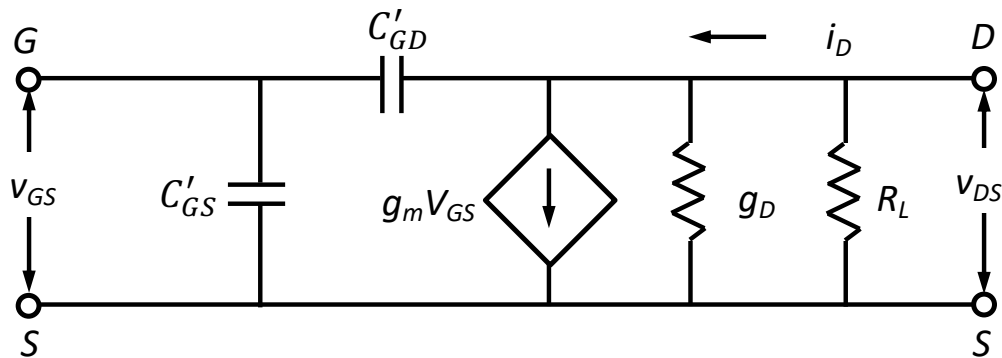
BG/TC



- *p* or *n* channel?
- $L/W = 10 \mu\text{m}/100 \mu\text{m}$
- Al gate
- $\text{AlO}_x$  gate insulator, 3.6 nm thick, PVD grown coated with alkylphosphonic acid SAM

# OTFT Bandwidth

Small signal equivalent circuit



$C_{GS}'$  = total gate-source capacitance (including parasitics)

$C_{GD}'$  = total gate-drain capacitance

$R_L$  = external load resistance

Small signal input (gate) current:  $i_{GS} = WLC_G \left. \frac{\partial v_{GS}}{\partial t} \right|_{V_{DS}} = j\omega (WLC_G) v_{GS} = j2\pi f (WLC_G) v_{GS}$

Small signal output (drain) current:  $i_D = g_D v_{DS} + g_m v_{GS} \Rightarrow i_D \approx g_m v_{GS}$  since  $g_D \rightarrow 0$

The maximum transistor bandwidth is reached when the current gain  $\left| \frac{i_D}{i_G} \right| = 1$

# Miller Capacitance and Gain

The capacitance is equal to the input ( $C_{GS}$ ) in parallel with the output capacitance ( $C_{GD}$ ) “amplified” by the circuit gain,  $A_v$ , that is:

$$C_G = C_{GS} + C_{GD} (1 + A_v)$$

where 
$$A_v = \frac{\partial v_{DS}}{\partial v_{GS}} = \frac{\partial v_{DS}}{\partial i_D} \frac{\partial i_D}{\partial v_{GS}} = \left( R_L \parallel \frac{1}{g'_D} \right) g_m$$

$$C_M = C_{GD} (1 + A_v)$$

This amplified output capacitance is called the “Miller capacitance” or the “Miller effect”

But the output conductance is small:  $R_L \parallel \frac{1}{g'_D} \rightarrow R_L$

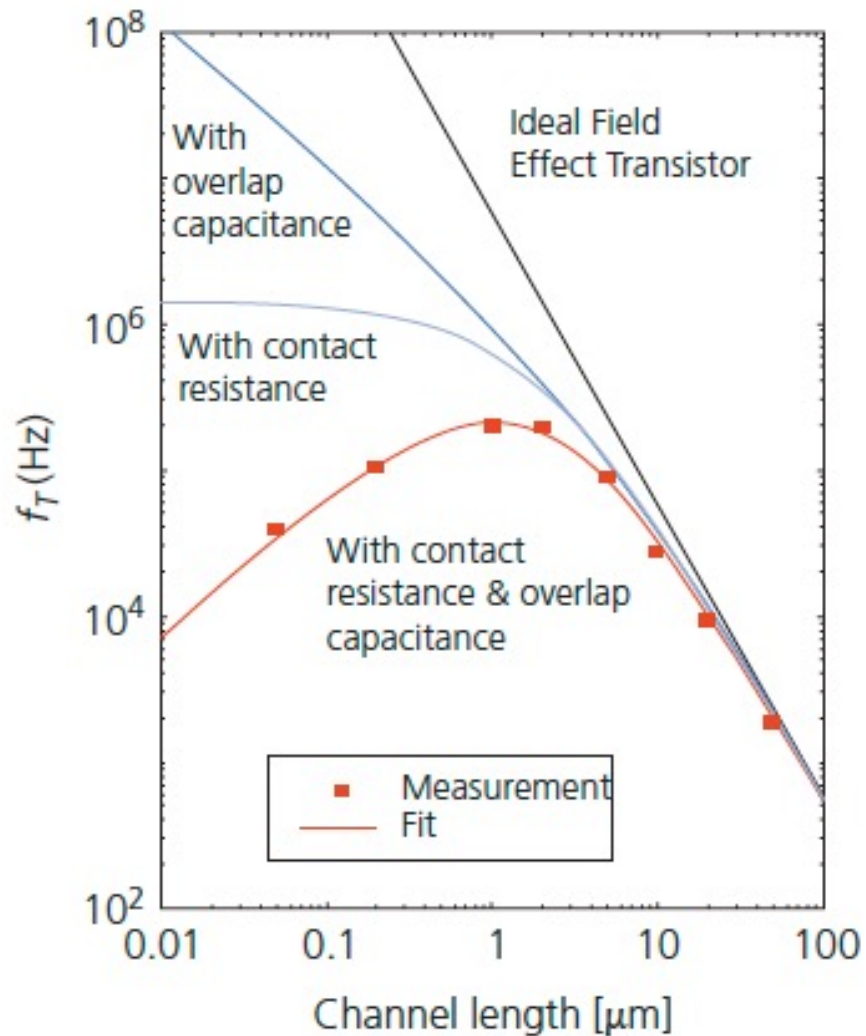
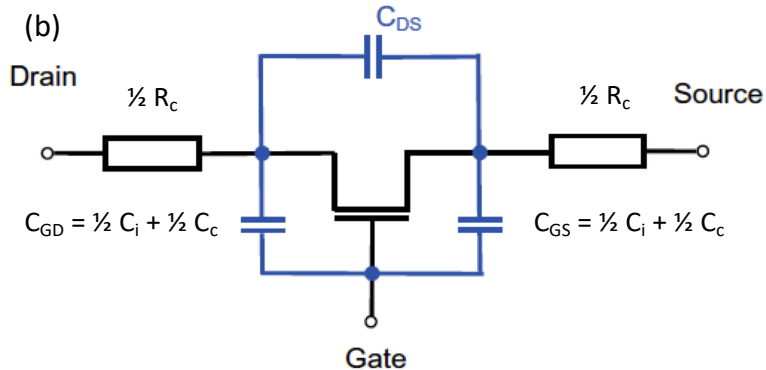
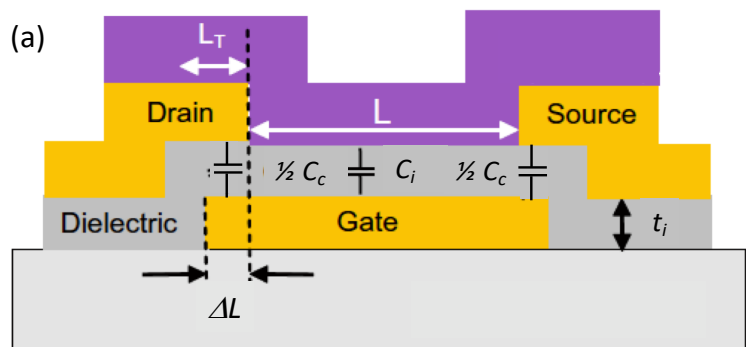
From these expressions, we get the cutoff, or transfer frequency:

$$f_T = \frac{g_m}{2\pi WLC_G} = \frac{g_m}{2\pi WL(C_{GS} + C_M)}$$



# Capacitance and Frequency Response

Sources of parasitic capacitances



# Combining Effects of Resistance and Capacitance

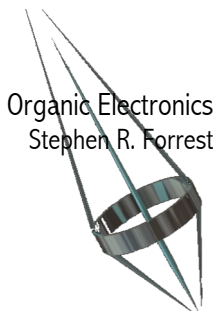
The transconductance and output conductances are reduced by drain and source contact resistances

$$g'_m = \frac{g_m}{1 + r_S g_m} \quad g'_D = \frac{g_D}{1 + (r_S + r_D) g_D}$$

As is the frequency response frequency response

$$f_T = \frac{\mu_{FE0} (V_{GS} - V_T)}{2\pi L (L + \Delta L)} \left[ \frac{1}{1 + W \mu_{FE0} C_G (V_{GS} - V_T) R_C / L} \right]$$

Where the total contact resistance is the series contributions from S and D:  $R_C = r_S + r_D$





# High Bandwidth OTFTs

